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(12) **United States Design Patent** (10) **Patent No.:** **US D924,823 S**
Saiki et al. (45) **Date of Patent:** **** Jul. 13, 2021**

(54) **ADIABATIC PLATE FOR SUBSTRATE PROCESSING APPARATUS**

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(30) **Foreign Application Priority Data**

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(51) **LOC (13) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D13/102, 182, 199; D8/19, 20, 366;
D5/99

CPC C23C 16/4582; H01L 21/67303; H01L 21/67309; H01L 21/6875; B32B 15/08

See application file for complete search history.

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(57) **CLAIM**

We claim the ornamental design for an adiabatic plate for substrate processing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a front, bottom and right side perspective view of an adiabatic plate for substrate processing apparatus showing our new design;

FIG. 2 is a front elevational view thereof;

FIG. 3 is a rear elevational view thereof;

FIG. 4 is a top plan view thereof;

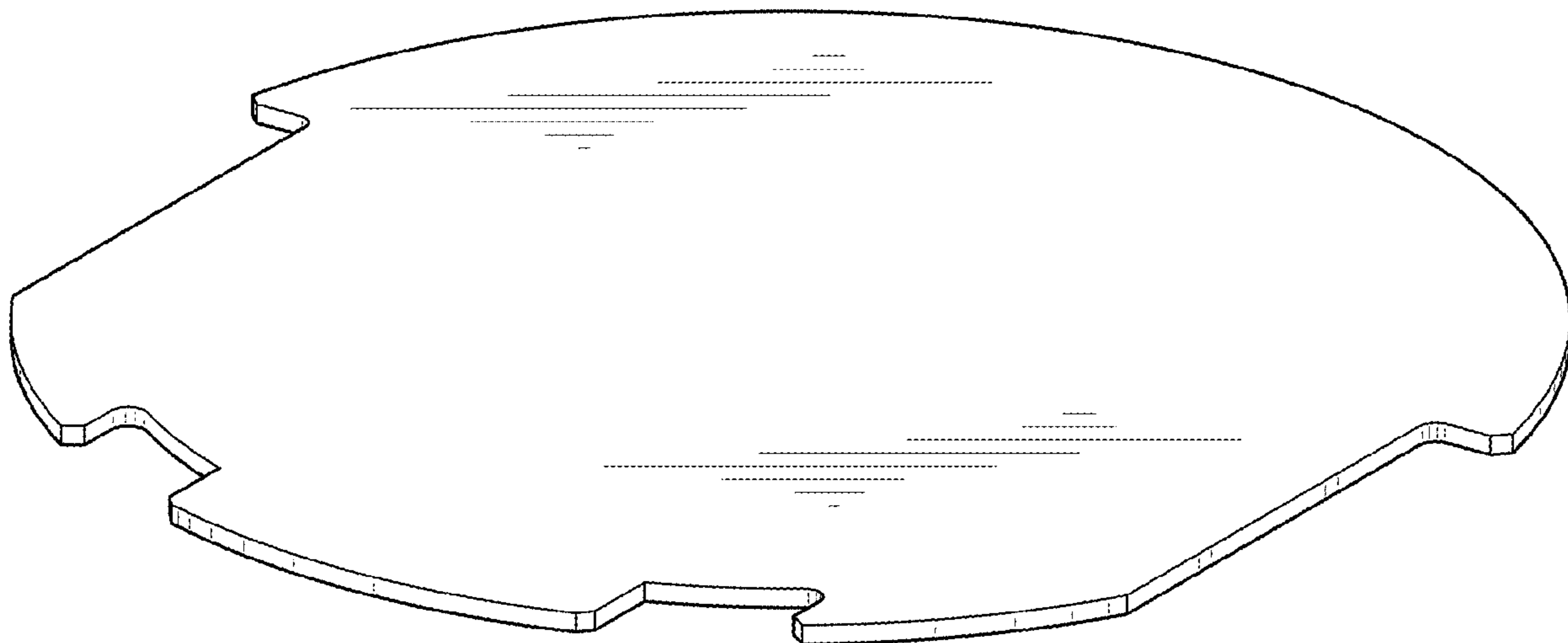
FIG. 5 is a bottom plan view thereof;

FIG. 6 is a left side elevational view thereof;

FIG. 7 is a right side elevational view thereof; and,

FIG. 8 is a cross-sectional view take along line 8-8 in FIG. 2.

1 Claim, 5 Drawing Sheets



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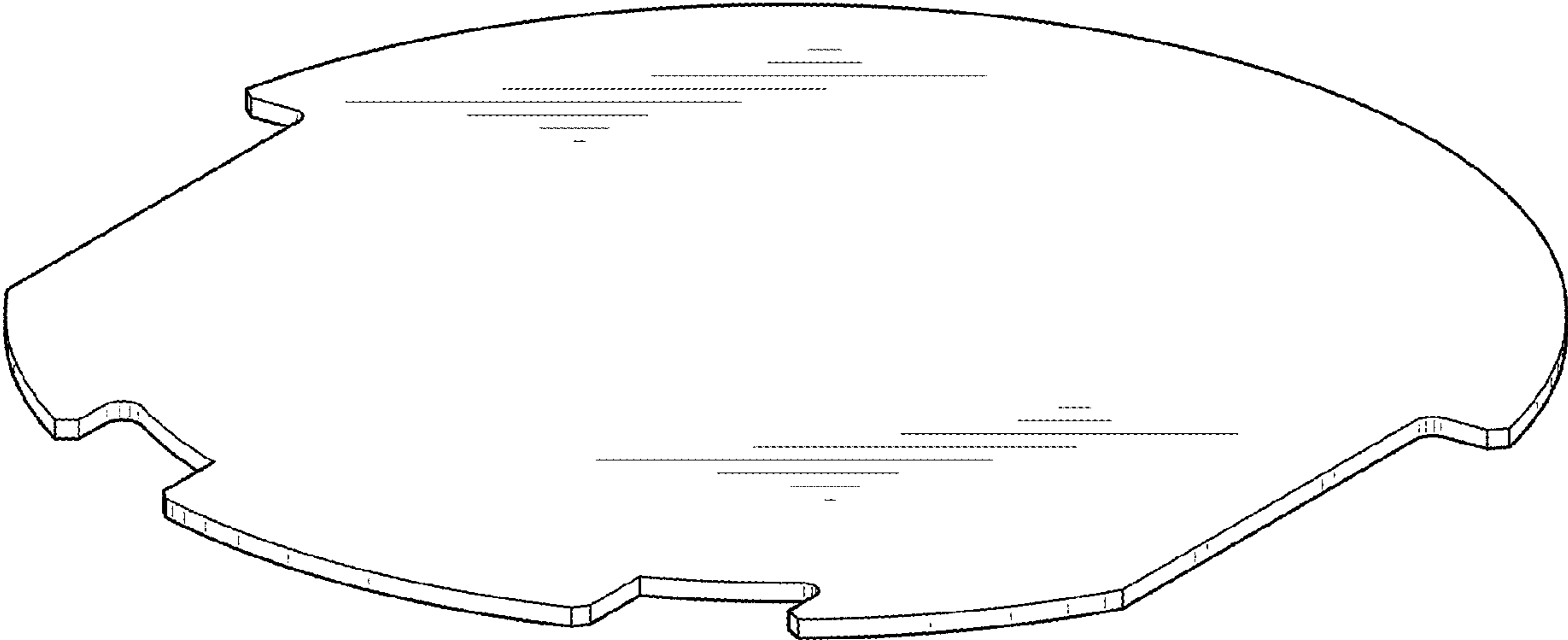


FIG. 1

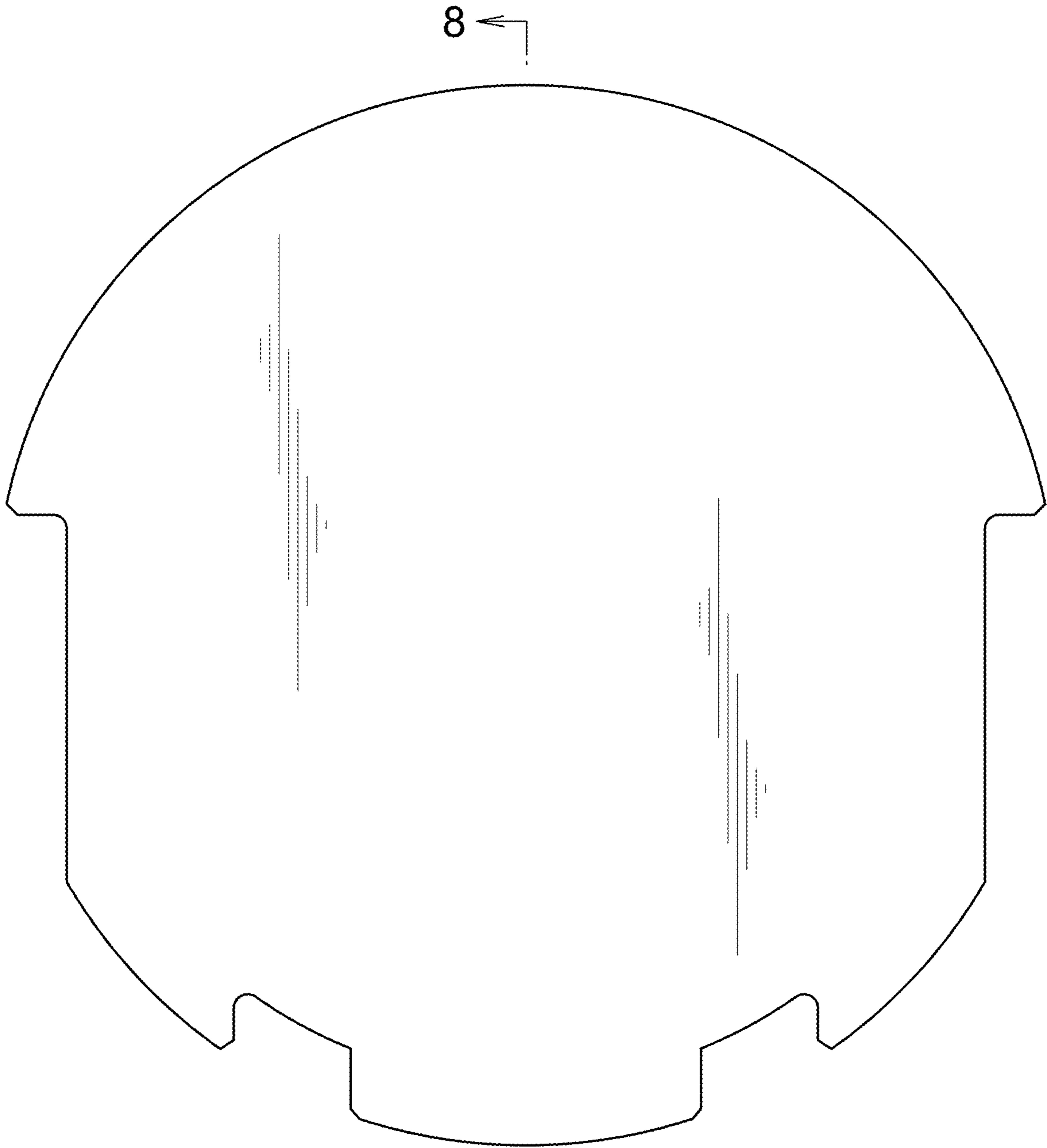


FIG. 2

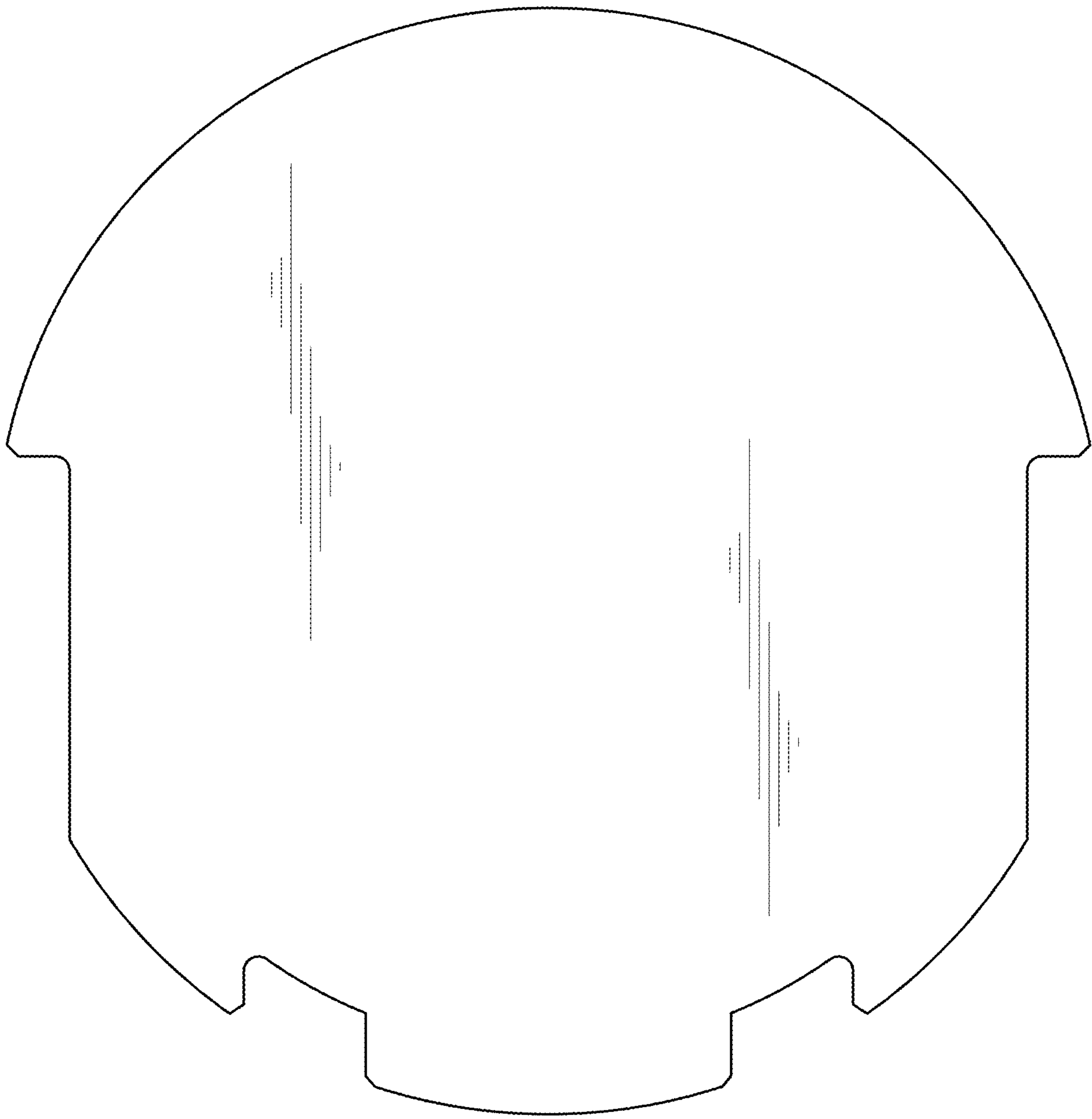


FIG. 3

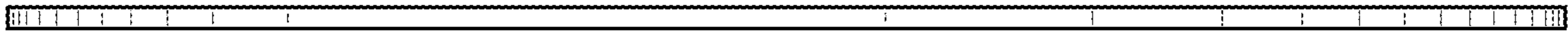


FIG. 4

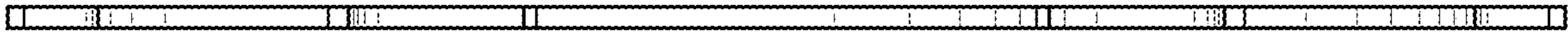


FIG. 5



FIG. 6



FIG. 7



FIG. 8